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Simulated multi-crystalline silicon solar cells with aluminum back surface field

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ABSTRACT

In photovoltaic solar cells manufacturing, we are confronted to the perpetual challenge for conversion efficiency enhancing.

We propose in this work to quantify the back surface field aluminium (Al-BSF) rear contact effect deposited by screen printing metallization.

Al-BSF numerical simulation has been performed by the use of softwares dedicated to photovoltaic like PC1D, SCAPS 2.7 and AFORS-HET.

In this work, a $\text{SiN}_x/\text{Si}(n^+)/\text{Si}(p)/\text{Si}(p^+)$ structure is studied. This means that we have a classical junction np passivated at the front face with SiN_x anti-reflective coating (ARC) and at the rear face a screen printed Aluminium contact.

The back Al-BSF, must to be thick (no least $10\mu\text{m}$) and highly p-doped (holes concentration between 10^{18} and 10^{19} cm^{-3}) in order to reduce effective rear recombination velocity, yielding to an enhancement of the Al layer performance.

Were inserted in the software parameters data: the lifetime measured for the inner bulk ($\tau_n=30\mu\text{s}$ and $\tau_p=90\mu\text{s}$) with Al diffusion ($10.8\mu\text{m}$ deep).

For emitter doping equals to $1.5*10^{20}\text{ cm}^{-3}$, front surface recombination velocity $S_f=8600\text{ cm/s}$ and the effective minority diffusion length $L_{\text{eff}}=227\mu\text{m}$.

After simulation of the input parameters, an efficiency of 18.0% is obtained by PC1D, in good accordance with the results presented in the literature. While the obtained efficiencies results with AFORS-HET and SCAPS 2.7 are 17.15% and 18.73% respectively. A rapprochement occurs between PC1D and SCAPS quantum efficiency curves with begin values $\sim 70\%$ QE while AFORS-HET is so far with $\sim 34\%$ QE.

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KEYWORDS

Solar cells;
Multi-crystalline silicon;
BSF;
PC1D;
SCAPS;
AFORS-HET;
Aluminium.

INTRODUCTION

Multi-crystalline silicon solar cells represent an unavoidable alternative to mono-crystalline silicon for large

scale industrial fabrication^[1,2]. However, multi-crystalline silicon properties are really different than mono-crystalline Czochralski (CZ) or Float zone (FZ) silicon growth. This is due essentially to the grain boundary

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presence which reduces the diffusion length and enhances the defects concentration.

Aluminum is generally used as back contact in photovoltaic cells thanks to its properties. It creates a heavily doped p⁺ region that provides a good (low resistivity) ohmic contact on the p-type silicon forming a back surface field^[3]. As we know, the eutectic point of Al-Si diagram occurs at T_E=577°C and its melting point is 660°C. In solar cells technology, we work at temperatures higher than the eutectic point and the melting point of aluminium. So, during the heating process, silicon dissolves in aluminium for T<T_E and continues to dissolve for T>T_E. While in the cooling process, the silicon quantity exceeding the eutectic composition will form the well known p⁺ BSF layer. Its thickness is of about 10µm.

A highly doped BSF permits to reduce the back recombination velocity at the contact metal-semiconductor. But very high doping exceeding 5.10¹⁹ may have the inverse effect^[4].

In this work, we propose to simulate a BSF in the multi-crystalline silicon structure SiN_x/Si(n⁺)/Si(p)/Si(p⁺) by the employment of three main photovoltaic dedicated softwares such: PC1D version 5.9, SCAPS version 2.7 and AFORS-HET version 2.2.

PC-1D program solves the nonlinear equations of quasi one-dimensional transport of electrons and holes in semiconductor devices, including photovoltaic devices in one dimension by using the finite element method^[5]. While SCAPS-1D program solves the equations for structures containing a number of semiconductor layers which have an arbitrary doping profile (as a function of the position) with an arbitrary distribution of energy levels deep donors or acceptors in different types of illumination. Iterations resolutions equations are made until algorithm convergence^[6,7].

AFORS-HET allows to model homo- as well as hetero-junction devices. An arbitrary sequence of semiconducting layers can be modelled. A variety of boundary conditions can be chosen. The program solves the one dimensional semiconductor equations in steady-state and for a small sinusoidal ac-perturbation^[8].

DEVICE MODELLING

The structure to model is composed of multi-crystal-

line silicon wafer type p which undergoes phosphorus diffusion at the front face in order to create a n⁺/p junction. In our case, we will insert the real technological parameters used in our laboratory such a junction depth of 0.7µm and 1.85 10²⁰ cm⁻³ electrons concentration. A passivated and ARC layer of SiN_x (thickness: 79 nm and refractive index 2) is deposited. The rear contact forms a BSF by creating the junction P⁺/P. Figure 1 below illustrates the modelled structure SiN_x/Si(n⁺)/Si(p)/Si(p⁺).

In industrial solar cells covered with screen printed aluminum, forming an Al-BSF, the rear contact has a back reflectance of 65% and a back recombination velocity (BSRV) of 1000 cm/s on 1Ωcm silicon wafer^[9].

The back Al-BSF must be thick (no least 10µm)^[10] and highly doped (holes concentration p between 10¹⁸ and 10¹⁹ cm⁻³) in order to reduce effective rear recombination velocity^[11], yielding to an enhancement of the Al layer performance.

We insert for Al-BSF layers the lifetime measured for the inner bulk (τ_n=30 µs and τ_p=90 µs) for multi-crystalline silicon cells with Aluminum diffusion of 10.8 µm in depth^[12]. TABLE 1 resumes the input data used for modeling the multi-crystalline BSF structure.

TABLE 1 : Input data for PC1D, SCAPS and AFORS-HET.

Device	
Device area	1cm ²
Single layer Anti-reflective coating ^[13] Front reflexion	n=2.0 t=79nm
ABSORBER REGION	
Thickness	280µm ^[14]
Material	From Si.mat
Dielectric constant	11.9
Band gap	1.124 eV
Intrinsic concentration at 300K	1E10 cm ⁻³
Refractive index	3.58
Absorption coefficient	From internal model
Free carrier absorption	enabled
P-type background doping	1E16
Front diffusion	N-type 1.85E20 junction n/p=0.7µm
1 st rear diffusion	P-type 1E19 junction p+/p=10µm
Bulk recombination	τ _n =30µs, τ _p =90µs
Front surface recombination	S _n =S _p =8600 cm/s ^[15]
Rear surface recombination	S _n =S _p =1000 cm/s ^[9]
Excitation	
Excitation from	One-sun AM1.5
Constant intensity	0.1 Wcm ⁻²

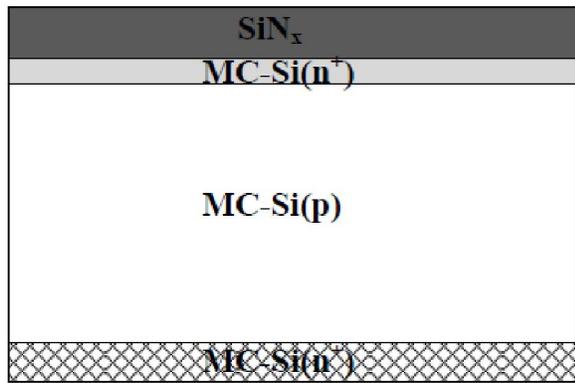


Figure 1 : $\text{SiN}_x/\text{Si}(n^+)/\text{Si}(p)/\text{Si}(p^+)$ multi-crystalline silicon based solar cell proposed to simulation.

RESULTS & DISCUSSION

After inserting the input parameters of the structure $\text{SiN}_x/\text{Si}(n^+)/\text{Si}(p)/\text{Si}(p^+)$. The obtained results $I(V)$ and quantum efficiency curves are represented in Figure 2, Figure 3 and Figure 4 for PC1D, SCAPS and AFORS-HET.

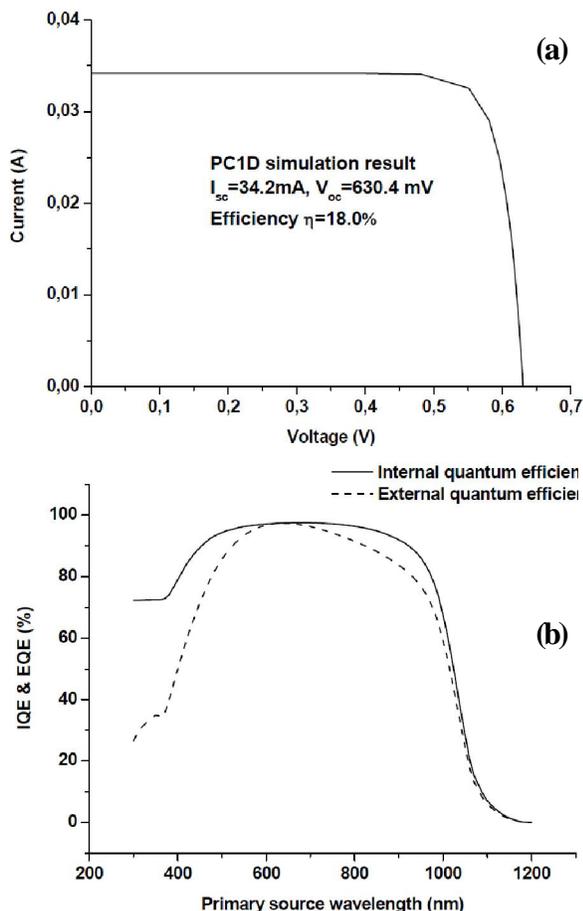


Figure 2 : PC1D 5.9 simulation results for $\text{SiN}_x/\text{Si}(n^+)/\text{Si}(p)/\text{Si}(p^+)$: (a) $I(V)$, (b) quantum efficiency.

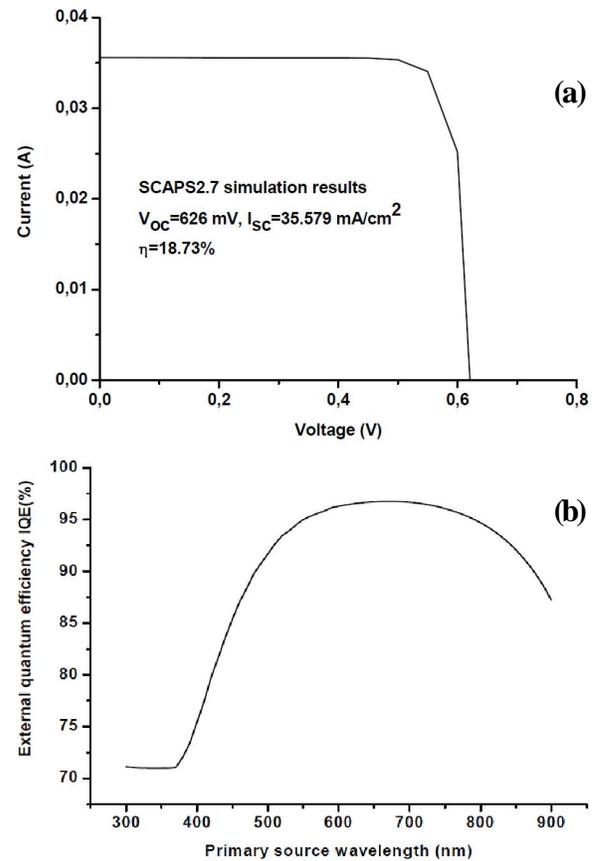


Figure 3 : SCAPS 2.7 simulation results for $\text{SiN}_x/\text{Si}(n^+)/\text{Si}(p)/\text{Si}(p^+)$: (a) $I(V)$, (b) quantum efficiency.

The obtained results are summarized in the TABLE 2 below:

Conventional structures without BSF give a conversion efficiency around 14%, as developed by Van Sark et al.^[16].

It is so therefore clear that a structure with BSF increases the conversion efficiency until reaching 17 to 18% depending on the used software.

The question that arises: why is there a difference in the results depending on the software?

For PC1D, an efficiency of 18% was obtained while SCAPS give us 18.73% and AFORS-HET 17.15%. Concerning the quantum efficiency, as represented in Figures 2b, 3b and 3c, one can remark that the curves have the same shape but for:

- PC1D, the first level occurs at approximately 350nm with 72.4% QE and reaches a maximum at 97.51% for 1060nm.
- SCAPS, the first level occurs at approximately 350nm with 71.0% QE and reaches a maximum at 96.71% for 900nm.

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- AFORS-HET, the first level occurs at approximately 350nm with 34% QE and reaches a maximum at 98% for 1100nm.

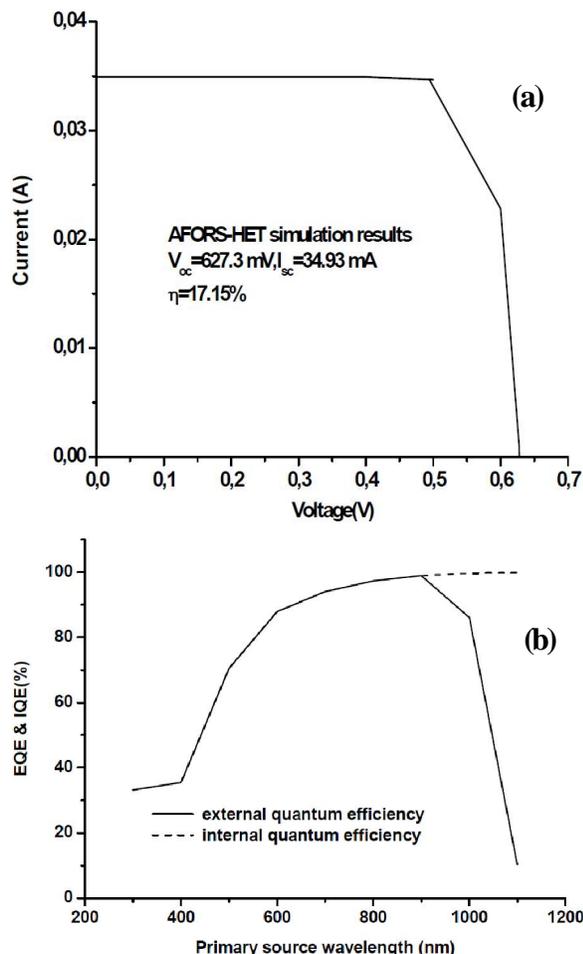


Figure 4 : AFORS-HET simulation results for $\text{SiN}_x/\text{Si}(n^+)/\text{Si}(p)/\text{Si}(p^+)$: (a) $I(V)$, (b) quantum efficiency.

TABLE 2 : $\text{SiN}_x/\text{Si}(n^+)/\text{Si}(p)/\text{Si}(p^+)$ simulation results summary by using PC1D, SCAPS and AFORS-HET.

Software	Voc (mV)	Isc (mA)	FF (%)	η (%)
Without BSF ^[16]	602.8	31.19	77.07	14.19
PC1D	630.4	34.2	83.48	18.00
SCAPS 2.7	626	35.57	84.05	18.73
AFORS-HET	627.3	34.93	78.25	17.15

We remark a rapprochement between PC1D and SCAPS quantum efficiency curves with begin values ~ 70% QE while AFORS-HET is so far with ~ 34% QE.

The PC1D is mainly dedicated to silicon. It is well suitable for our structure to simulate. The obtained values coincide with the literature^[14]. But don't take into account the deep interface states and profound bulk states like in AFORS- HET and SCAPS^[17].

While the recent version 2.7 of SCAPS treat thick substrates and therefore is suitable to our problem. But with a limit for the high degeneracy at the front junction to 10^{20} cm^{-3} . So our value $1.85 * 10^{20}$ can not be taken into consideration.

Regarding to AFORS-HET, it is obvious that it is rather dedicated to hetero-junction structures like HIT layers and thin films than our kind of homo-junction with thick substrate.

CONCLUSION

Multi-crystalline silicon solar cells with back surface field BSF and SiN_x anti-reflective coating have been simulated by using photovoltaic dedicated softwares.

Three programs have been employed: PC1D; SCAPS and AFORS-HET.

By combining the experimental values with those obtained in the literature, an input data table for BSF multi-crystalline silicon has been formed.

The obtained conversion efficiencies are: 18%, 18.73% and 17.15% for PC1D, SCAPS and AFORS-HET respectively.

PC1D and SCAPS quantum efficiency curves converge with begin values ~ 70% QE while AFORS-HET is so far with ~ 34% QE.

One can deduce that PC1D is the most suitable software for silicon. While the recent version 2.7 of SCAPS treats thick substrates but has a limit for the high degeneracy electron concentration.

AFORS-HET is the non adaptable software for our BSF structure because it is dedicated to hetero-junction structures like HIT layers and thin films than our kind of homo-junction with thick substrate.

In conclusion, simulation with PC1D and SCAPS are more suitable to the structure $\text{SiN}_x/\text{Si}(n^+)/\text{Si}(p)/\text{Si}(p^+)$ than afors-Het.

The BSF is a significant parameter in increasing the conversion efficiency of solar cells based on multi-crystalline silicon. It requires a finer thickness of silicon wafer which should be greater than $200 \mu\text{m}$ for a good substrate quality^[18].

Experimentally, the BSF is easily integrated into the multi-crystalline silicon solar cells fabrication process, since simultaneous annealing for Ag and Al contacts and SiN_x passivation can be done^[19].

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